



## *Future Normal in Semiconductor*

2025-02-14(금), 10:55-12:40

좌장: 추후업데이트 예정

### K. Memory (Design & Process Technology) 분과

#### [FJ2-K] Oxide Channel based Memory Technology

<p>FJ2-K-1 10:55-11:10</p>	<p><b>Photoprogrammable OFET Memory Devices based on IGZO Floating Gate</b> Gyeongho Lee<sup>1,2</sup>, Dong Hyun Lee<sup>3</sup>, and Hocheon Yoo<sup>3,4</sup> <sup>1</sup>Department of Semiconductor Total Solution Center, KICET, <sup>2</sup>Department of Materials Science and Engineering, Korea University, <sup>3</sup>Department of Electronic Engineering, Gachon University, <sup>4</sup>Department of Semiconductor Engineering, Gachon University</p>
<p>FJ2-K-2 11:10-11:25</p>	<p><b>Oxide Channel-Based Ferroelectric NAND Device with Enhanced Memory Window Using a Source-Tied Metal Cover Structure</b> Hongrae Joh, Giuk Kim, Jihye Ock, Seungyeob Kim, Sangmok Lee, Sangho Lee, and Sanghun Jeon<sup>1</sup> School of Electrical Engineering, KAIST</p>
<p>FJ2-K-3 11:25-11:40</p>	<p><b>Comparative Evaluation of the Impact of WL Off Voltage on BL Disturbance in SOI and IGZO Cell Transistors for 4F2 DRAM Application</b> Seong Hoon Jeon, Wonjung Kim, Seungki Kim, Soohong Eo, Sae Him Jung, Jong-Ho Bae, Sung-Jin Choi, Dong Myong Kim, and Dae Hwan Kim School of Electrical Engineering, Kookmin University</p>
<p>FJ2-K-4 11:40-11:55</p>	<p><b>Demonstration of Amorphous InGaZnOx 2T-DRAM Array and Analog Operation Capability for Processing-In-Memory Application</b> Hyunwook Jeong<sup>1</sup>, Junseong Park<sup>1</sup>, Haesung Kim<sup>1</sup>, Hyojin Yang<sup>1</sup>, Yubin Choi<sup>1</sup>, Hwan Jin Kim<sup>1</sup>, Sujong Kim<sup>1</sup>, Sung-Jin Choi<sup>1</sup>, Dae Hwan Kim<sup>1</sup>, Dong Myong Kim<sup>2</sup>, Seongjae Cho<sup>3</sup>, and Jong-Ho Bae<sup>1</sup> <sup>1</sup>School of the Electronic Engineering, Kookmin University, <sup>2</sup>Department of Advanced Technology, DGIST, <sup>3</sup>Department of Electronic and Electrical Engineering, Ewha Womans University</p>



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<p>FJ2-K-5 11:55-12:10</p>	<p><b>Comparative Optimization of Synaptic Characteristics in IGZO-based Memristors through Interface Engineering with Metal Electrode</b> Jae Woo Lee, Dong Hyeop Shin, Wonjung Kim, Seung Joo Myoung, Changwook Kim, Jong-Ho Bae, Sung-Jin Choi, Dong Myong Kim, and Dae Hwan Kim School of Electrical Engineering, Kookmin University</p>
<p>FJ2-K-6 12:10-12:25</p>	<p><b>Highly Linear and Symmetric Multilevel IGZO 2T Synaptic Device Utilizing Identical Potentiation and Depression Pulses</b> Suwon Seong<sup>1</sup>, Taejun Ha<sup>1</sup>, and Yoonyoung Chung<sup>1,2,3</sup> <sup>1</sup>Department of Electrical Engineering, <sup>2</sup>Department of Semiconductor Engineering, <sup>3</sup>Center for Semiconductor Technology Convergence, POSTECH</p>
<p>FJ2-K-7 12:25-12:40</p>	<p><b>Disturbance-Free Parallel Programming for Multilevel IGZO 2T Synapse</b> Taejun Ha<sup>1</sup>, Suwon Seong<sup>1</sup>, and Yoonyoung Chung<sup>1,2,3</sup> <sup>1</sup>Department of Electrical Engineering, <sup>2</sup>Department of Semiconductor Engineering, <sup>3</sup>Center for Semiconductor Technology Convergence, POSTECH</p>